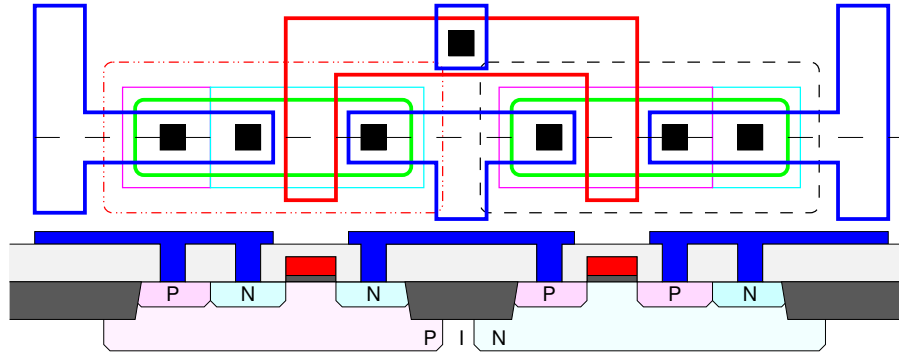


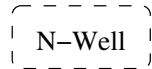
Twin Tub CMOS Process
with explicit N+ implant mask



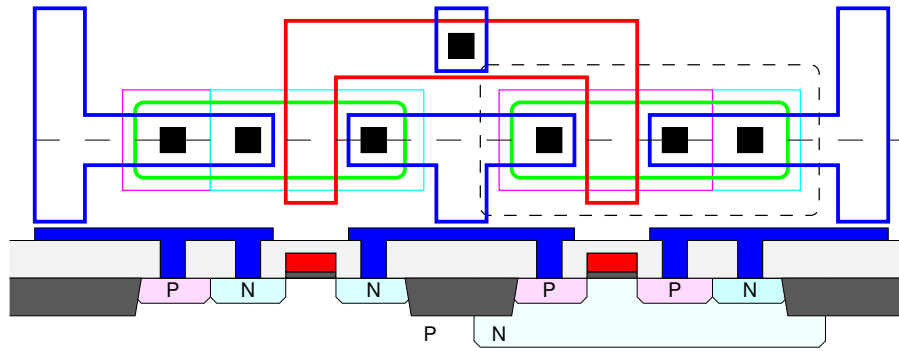
includes combined contact and tap



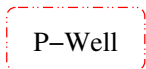
N-Well CMOS Process
with explicit N+ implant mask



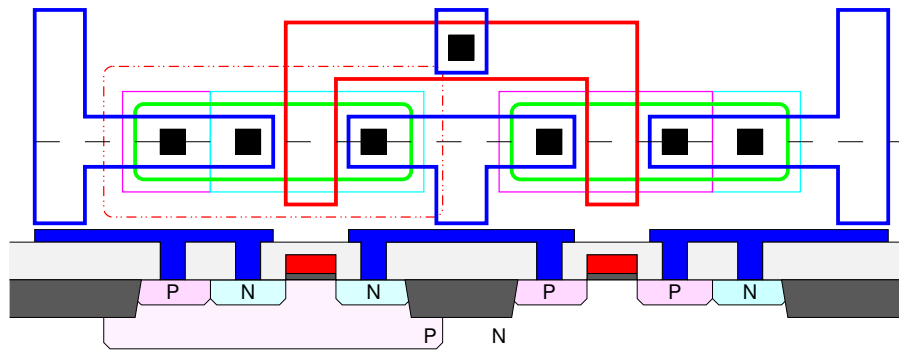
includes combined contact and tap



P-Well CMOS Process
with explicit N+ implant mask



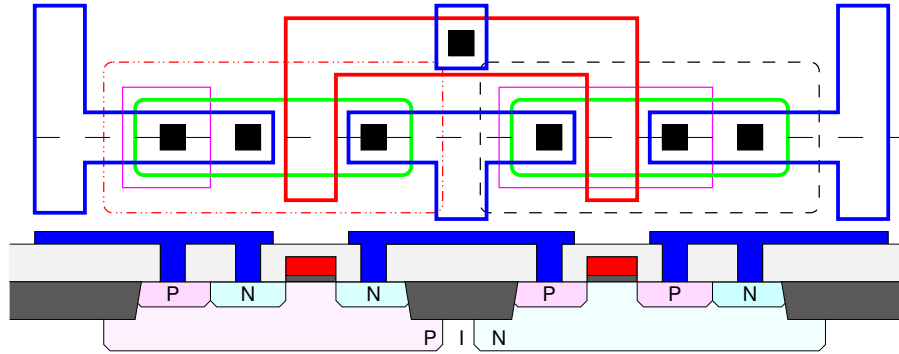
includes combined contact and tap



Twin Tub CMOS Process
without explicit N+ implant mask



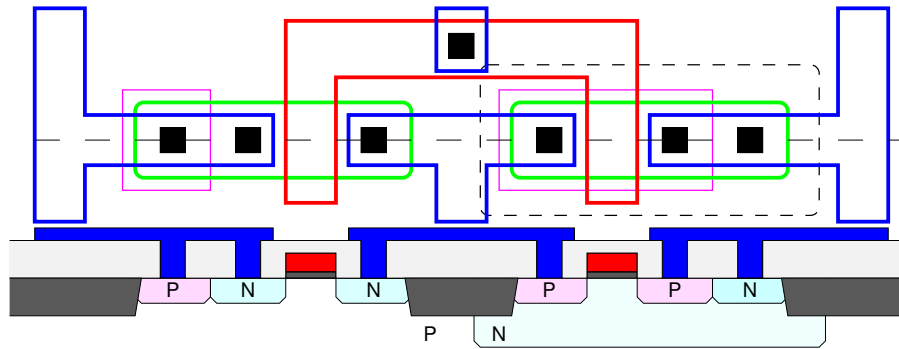
includes combined contact and tap



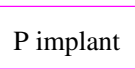
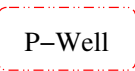
N-Well CMOS Process
without explicit N+ implant mask



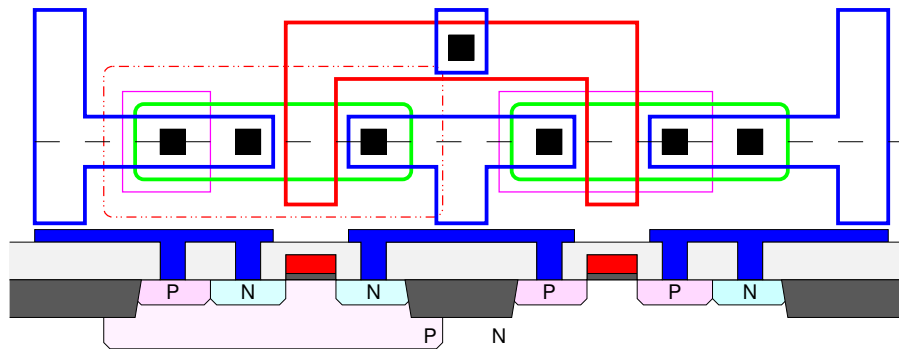
includes combined contact and tap



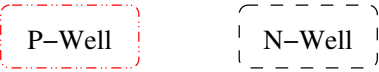
P-Well CMOS Process
without explicit N+ implant mask



includes combined contact and tap

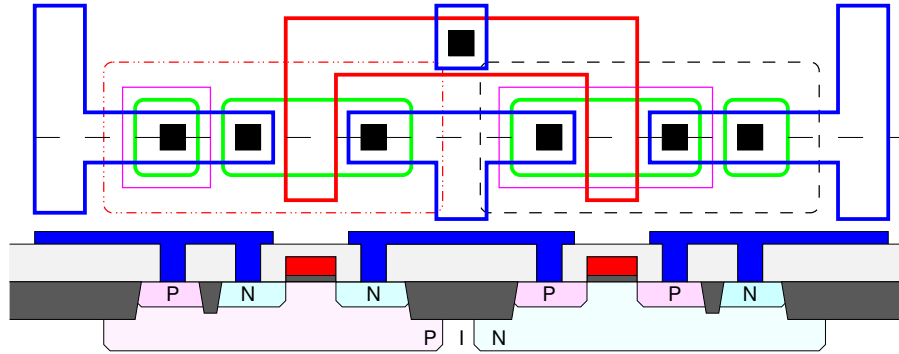


Twin Tub CMOS Process
without explicit N+ implant mask



P implant (pink box)

includes separate contact and tap

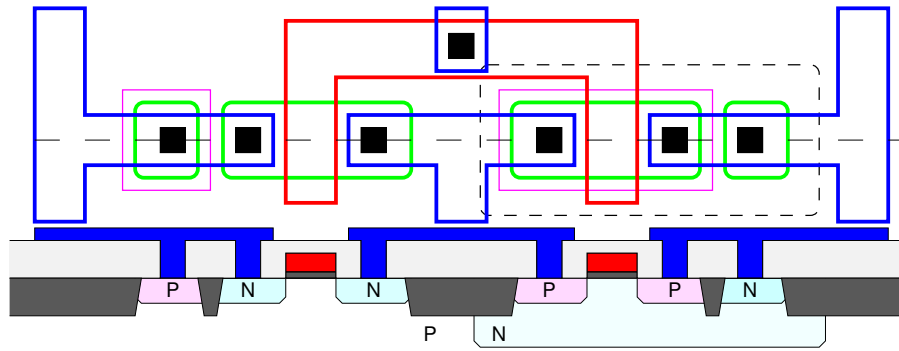


N-Well CMOS Process
without explicit N+ implant mask

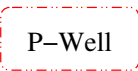


P implant (pink box)

includes separate contact and tap



P-Well CMOS Process
without explicit N+ implant mask



P implant (pink box)

includes separate contact and tap

